

Rev. 04/03

Docket No. ELM-1 Cont. 13

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Glenn J. Leedy  
Application No.: 10/724,282 Confirmation No.: 5846  
Filed : December 19, 2003  
For : MEMBRANE 3D IC FABRICATION  
Group Art Unit : 2814  
Examiner : Not yet assigned

New York, New York  
July 16, 2004

Hon. Commissioner for Patents  
P.O. Box 1450  
Alexandria, Virginia 22313-1450

TRANSMITTAL LETTER FOR  
INFORMATION DISCLOSURE STATEMENT

Sir:

Transmitted herewith is an Information Disclosure Statement in the above-identified application. This Statement is submitted:

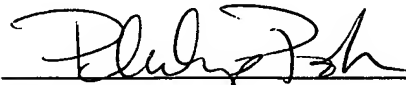
- ☐ [ ] within three months of the application filing date;
- ☒ [X] more than three months from the application filing date but before the mailing date of the first Office Action on the merits.

In accordance with 37 C.F.R. § 1.97, submission of this Statement requires no fee. However, if for any reason a fee is due, the Director is hereby authorized to charge payment of any fees required in connection with this

Information Disclosure Statement to Deposit Account

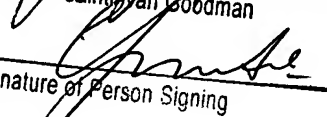
No. 06-1075. A duplicate copy of this letter is transmitted herewith.

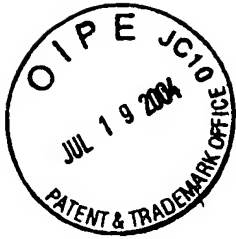
Respectfully submitted,



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P.O. Box 1450  
Alexandria, VA 22313-1450 on

July 16, 2004  
Claire J. Saintilvan Goodman  
  
Signature of Person Signing



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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Alexandrian, Virginia 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

In accordance with 37 C.F.R. §§ 1.56 and 1.97,  
applicant wishes to call the attention of the Examiner to  
the following documents:

U.S. Patents

Fujii et al.	Re. 34,893	04/04/95
Foster	2,915,722	12/01/59
Farrand	3,202,948	08/24/65
Lesk	3,559,282	02/02/71
Burkhardt	3,560,364	02/02/71
Emmasingel	3,602,982	09/07/71
Medicus	3,615,901	10/26/71
Napoli et al.	3,716,429	02/13/73
Krishna et al.	3,777,227	12/14/73
Kuipers	3,868,565	02/25/75
Yerman	3,922,705	11/25/75
Wanlass	3,997,381	12/14/76
Stein	4,070,230	01/24/78
Greenwood et al.	4,131,985	01/02/79
Hauser, Jr., et al.	4,142,004	02/27/79
Hoeberechts	4,251,909	02/24/81

Kubacki	4,262,631	04/21/81
Shioya et al.	4,394,401	07/19/83
Trenkler et al.	4,401,986	08/30/83
Thomas et al.	4,416,054	11/22/83
Takagi et al.	4,539,068	09/03/85
Reid et al.	4,585,991	04/29/86
Yasumoto et al.	4,612,083	09/16/86
Belanger et al.	4,617,160	10/14/86
Shimizu et al.	4,618,397	10/21/86
Schmitz	4,618,763	10/21/86
Christensen	4,663,559	05/05/87
Burns et al.	4,684,436	08/04/87
Hatada	4,693,770	09/15/87
Maeda et al.	4,702,336	10/27/87
Seibert et al.	4,702,936	10/27/87
Go	4,706,166	11/10/87
Stevenson	4,721,938	01/26/88
Reid	4,761,681	08/02/88
Holmen et al.	4,784,721	11/15/88
Freeman	4,810,673	03/07/89
Mattox et al.	4,825,277	04/25/89
Tam et al.	4,857,481	08/15/89
Leedy	4,924,589	05/15/90
Borel et al.	4,940,916	07/10/90
Borel et al.	ReB14,940916	11/26/96
Vranish et al.	4,950,987	08/21/90
Lee et al.	4,952,446	08/18/90
Rokos	4,954,865	09/04/90
Shinomiya	4,957,882	09/18/90
Young et al.	4,965,415	10/23/90
Mauger	4,966,663	10/30/90
Leedy	4,994,735	02/19/91
Keogh et al.	5,008,619	04/16/91
Allen et al.	5,010,024	04/23/91
Leedy	5,020,219	06/04/91
Leedy	5,034,685	07/23/91
Greenwald et al.	5,070,026	12/03/91
Findler et al.	5,071,510	12/10/91
Machado et al.	5,098,865	03/24/92
Leedy	5,103,557	04/14/92
Mauger	5,110,373	05/05/92
Eichelberger	5,111,278	05/05/92
Chan et al.	5,116,777	05/26/92
Miller	5,130,894	07/14/92
Roy	5,132,244	07/21/92
Hadwin	5,151,775	09/29/92
Henager, Jr., et al.	5,156,909	10/20/92

Zimmerman	5,203,731	04/20/93
Leedy	5,225,771	07/06/93
Bower et al.	5,236,118	08/17/93
Bureau et al.	5,262,351	11/16/93
Bertin et al.	5,270,261	12/14/93
Sanders	5,273,940	12/28/93
Tuckerman	5,274,270	12/28/93
Chebi et al.	5,279,865	01/18/94
Nakanishi et al.	5,284,796	02/08/94
Leedy	5,323,035	06/21/94
Wojnarowski	5,324,687	06/28/94
Leedy	5,354,695	10/11/94
MacDonald	5,363,021	11/08/94
Goossen	5,385,632	01/31/95
Nelson et al.	5,385,909	10/25/94
Shimoji	5,420,458	05/30/95
Miyake	5,424,920	06/13/95
Finnila	5,426,072	06/20/95
Akagi et al.	5,426,363	06/20/95
Yasohama et al.	5,432,444	07/11/95
Carson et al.	5,432,729	07/11/95
Hauck et al.	5,434,500	07/18/95
Leedy	5,451,489	09/19/95
Leedy	5,453,404	09/26/95
Gurtler et al.	5,457,879	10/17/95
Naruse	5,476,813	12/19/95
Gates	5,489,554	02/06/96
Bertin et al.	5,502,667	03/26/96
Leedy	5,512,397	04/30/96
Pati et al.	5,527,645	06/18/96
Koskenmaki et al.	5,529,829	06/25/96
Frye et al.	5,534,465	07/09/96
Toshiaki et al.	5,555,212	09/10/96
Ramm et al.	5,563,084	10/08/96
Leedy	5,571,741	11/05/96
Leedy	5,580,687	12/03/96
Ludwig et al.	5,581,498	12/03/96
Pierrat	5,582,939	12/10/96
Hornbeck	5,583,688	12/10/96
Leedy	5,592,007	01/07/97
Leedy	5,592,018	01/07/97
Heijboer	5,595,933	01/27/97
Noda	5,606,186	02/25/97
Tennant et al.	5,627,112	05/06/97
Leedy	5,629,137	05/13/97
Leedy	5,633,209	05/27/97
Val	5,637,536	06/10/97

Leedy	5,654,127	08/05/97
Leedy	5,654,220	08/05/97
Hudak et al.	5,656,552	08/12/97
Chen et al.	5,675,185	10/07/97
Ohara et al.	5,694,588	12/02/97
Leedy	5,725,995	03/10/98
Weise et al.	5,750,211	05/12/98
Bozso et al.	5,760,478	06/02/98
Okonogi	5,773,152	06/30/98
Rolfson	5,786,116	07/28/98
Zavracky et al.	5,793,115	08/11/98
Ray	5,831,280	11/03/98
Leedy	5,834,334	11/10/98
Leedy	5,840,593	11/24/98
Ito et al.	5,856,695	01/05/99
Sotokawa et al.	5,868,949	02/09/99
Leedy	5,869,354	02/09/99
Sweatt et al.	5,870,176	02/09/99
Davidson	5,880,010	03/09/99
Field et al.	5,882,532	03/16/99
Hübner	5,902,118	05/11/99
Leedy	5,915,167	06/22/99
Leedy	5,946,559	08/31/99
Leedy	5,985,693	11/16/99
Cutter et al.	5,998,069	12/07/99
Leedy	6,008,126	12/28/99
Leedy	6,020,257	02/01/00
Houston	6,045,625	04/04/00
Adamic, Jr.	6,084,284	07/04/00
Gardner et al.	6,097,096	08/01/00
Leedy	6,133,640	10/17/00
Tayanaka	6,194,245 B1	02/27/01
Aleshin et al.	6,197,456 B1	03/06/01
Leedy	6,208,545 B1	03/27/01
Patti	6,236,602 B1	05/22/01
Lin	6,261,728 B1	07/17/01
Leedy	6,288,561 B1	09/11/01
Leedy	6,294,909 B1	09/11/01

#### Foreign Patents

PCT	WO 98/19337	05/1998
UK	GB 2,215,168	09/1989
EPO	EP 0 189 976	08/1986
EPO	EP 0 731 525	09/1996
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JAPAN	JP 02-082564	03/1990
JAPAN	JP 04-083371	03/1992
JAPAN	JP 04-107964	04/1992
JAPAN	JP 402027600A	01/1990

#### Other Documents

"IC Tower Patent: Simple Technology Receives Patent on the IC Tower, a Stacked Memory Technology,"  
<http://www.simpletech.com/whatsnew/memory/@60824.htm> (1998).

Alloert, K., et al., "A Comparison Between Silicon Nitride Films Made by PCVD of  $N_2-SiH_4 / A_r$  and  $N_2-SiH_4/He$ ," Journal of the Electrochemical Society, Vol. 132, No. 7, pp. 1763-1766, (July 1985).

Hendricks, et al., "Polyquinoline Coatings and Films: Improved Organic Dielectrics for IC's and MCM's," Eleventh IEEE/CHMT International Electronics Manufacturing Technology Symposium," pp. 361-265 (1991).

Knolle, W.R., et al., "Characterization of Oxygen-Doped, Plasma-Deposited Silicon Nitride," Journal of the Electrochemical Society, Vol. 135, No. 5, pp. 1211-1217, (May 1988).

Nguyen, S.V., "Plasma Assisted Chemical Vapor Deposited Thin Films for Microelectronic Applications, J. Vac. Sci. Technol. Vol. B4, No. 5, pp.1159-1167, (Sep/Oct. 1986).

Olmer, et al., "Intermetal Dielectric Deposition by Plasma Enhanced Chemical Vapor Deposition," Fifth IEEE/CHMT International Electronic Manufacturing Technology Symposium - Design-to-Manufacturing Transfer Cycle," pp. 98-99 (1988).

Runyan, W.R., "Deposition of Inorganic Thin Films," *Semiconductor Integrated Circuit Processing Technology*, p. 142 (1990).

Sze, S.M., "Surface Micromachining," *Semiconductor Sensors*, pp. 58-63 (1994).

Vossen, John L., "Plasma-Enhanced Chemical Vapor Deposition," *Thin Film Processes II*, pp. 536-541 (1991).

Wolf, Stanley, "Basic of Thin Films," *Silicon Processing for the VLSI Era*, pp. 115, 192-193 and 199 (1986).

Copies of the aforementioned documents are listed on the accompanying Form PTO-1449 (submitted in duplicate).

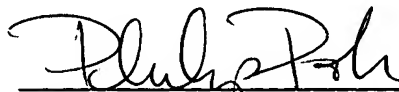
It is respectfully requested that these documents be:

(1) fully considered by the Patent and Trademark Office during the examination of this application; and (2) printed on any patent which may issue on this application.

Applicant requests that a copy of Form PTO-1449, as considered and initialized by the Examiner, be returned with the next communication.

Consideration of the foregoing in relation to this patent application is respectfully requested.

Respectfully submitted,



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July 16, 2004  
Claire J. Saint-Yvan Goodman

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FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE  
PATENT AND TRADEMARK OFFICEATTY. DOCKET NO.  
ELM-1 Cont. 13APPLICATION NO.  
10/724,282INFORMATION DISCLOSURE  
STATEMENT BY APPLICANTAPPLICANT  
Glenn J. LeedyCONFIRMATION NO.  
5846FILING DATE  
December 19, 2003GROUP  
2814

## U.S. PATENT DOCUMENTS

EXAMINE R INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	Re. 34,893	04/04/95	Fujii et al.	257	419	
	2,915,722	12/01/59	Foster	336	115	
	3,202,948	08/24/65	Farrand	336	115	
	3,559,282	02/02/71	Lesk	438	113	
	3,560,364	02/02/71	Burkhardt	324	207.12	
	3,602,982	09/07/71	Emmasingel	29	577	
	3,615,901	10/26/71	Medicus	148	11.5 R	
	3,716,429	02/13/73	Napoli et al.	156	17	
	3,777,227	12/14/73	Krishna et al.	257	578	
	3,868,565	02/25/75	Kuipers	324	207.26	
	3,922,705	11/25/75	Yerman	357	26	
	3,997,381	12/14/76	Wanlass	156	3	
	4,070,230	01/24/78	Stein	156	657	
	4,131,985	01/02/79	Greenwood et al.	29	580	
	4,142,004	02/27/79	Hauser, Jr. et al.	438	792	
	4,251,909	02/24/81	Hoeberechts	29	580	
	4,262,631	04/21/81	Kubacki	118	723MP	
	4,394,401	07/19/83	Shioya et al.	427	574	
	4,401,986	08/30/83	Trenkler et al.	340	870.32	
	4,416,054	11/22/83	Thomas et al.	29	572	
	4,539,068	09/03/85	Takagi et al.	156	614	
	4,585,991	04/29/86	Reid et al.	324	158 P	
	4,612,083	09/16/86	Yasumoto et al.	156	633	
	4,617,160	10/14/86	Belanger et al.	264	40.1	
	4,618,397	10/21/86	Shimizu et al.	156	628	
	4,618,763	10/21/86	Schmitz	250	211R	
	4,663,559	05/05/87	Christensen	313	336	
	4,684,436	08/04/87	Burns et al.	216	65	
	4,693,770	09/15/87	Hatada	156	151	

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not conformance and not considered. Include copy of this form with next communication to applicant.

FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. ELM-1 Cont. 13		APPLICATION NO. 10/724,282	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT				APPLICANT Glenn J. Leedy		CONFIRMATION NO. 5846	
				FILING DATE December 19, 2003		GROUP 2814	
	4,702,336	10/27/87	Maeda et al.	180	197		
	4,702,936	10/27/87	Seibert et al.	427	583		
	4,706,166	11/10/87	Go	361	403		
	4,721,938	01/26/88	Stevenson	338	4		
	4,761,681	08/02/88	Reid	357	68		
	4,784,721	11/15/88	Holmen et al.	156	647		
	4,810,673	03/07/89	Freeman	438	386		
	4,825,277	04/25/89	Mattox et al.	257	639		
	4,857,481	08/15/89	Tam et al.	438	619		
	4,924,589	05/15/90	Leedy	438	6		
	4,940,916	07/10/90	Borel et al.	313	306		
	Re B14,940,916	11/26/96	Borel et al.	315	306		
	4,950,987	08/21/90	Vranish et al.	324	207.23		
	4,952,446	08/18/90	Lee et al.	428	220		
	4,954,865	09/04/90	Rokos	257	378		
	4,957,882	09/18/90	Shinomiya	438	65		
	4,965,415	10/23/90	Young et al.	200	83 N		
	4,966,663	10/30/90	Mauger	205	656		
	4,994,735	02/19/91	Leedy	324	158		
	5,008,619	04/16/91	Keogh et al.	324	207.17		
	5,010,024	04/23/91	Allen et al.	438	659		
	5,020,219	06/04/91	Leedy	29	846		
	5,034,685	07/23/91	Leedy	324	158 F		
	5,070,026	12/03/91	Greenwald et al.	437	3		
	5,071,510	12/10/91	Findler et al.	156	647		
	5,098,865	03/24/92	Machado et al.	438	788		
	5,103,557	04/14/92	Leedy	29	832		
	5,110,373	05/05/92	Mauger	148	33.2		
	5,111,278	05/05/92	Eichelberger	357	75		
	5,116,777	05/26/92	Chan et al.	438	234		
	5,130,894	07/14/92	Miller	361	393		
	5,132,244	07/21/92	Roy	438	477		

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not conformance and not considered. Include copy of this form with next communication to applicant.

FORM PTO-1449  U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. ELM-1 Cont. 13	APPLICATION NO. 10/724,282
	APPLICANT Glenn J. Leedy	CONFIRMATION NO. 5846
	FILING DATE December 19, 2003	GROUP 2814

	5,151,775	09/29/92	Hadwin	357	80	
	5,156,909	10/20/92	Henager, Jr. et al.	428	334	
	5,203,731	04/20/93	Zimmerman	445	24	
	5,225,771	07/06/93	Leedy	324	158	
	5,236,118	08/17/93	Bower et al.	228	193	
	5,262,351	11/16/93	Bureau et al.	437	183	
	5,270,261	12/14/93	Bertin et al.	437	209	
	5,273,940	12/28/93	Sanders	437	209	
	5,274,270	12/28/93	Tuckerman	257	758	
	5,279,865	01/18/94	Chebi et al.	427	574	
	5,284,796	02/08/94	Nakanishi et al.	437	183	
	5,323,035	06/21/94	Leedy	257	48	
	5,324,687	06/28/94	Wojnarowski	437	225	
	5,354,695	10/11/94	Leedy	438	411	
	5,363,021	11/08/94	MacDonald	315	366	
	5,385,909	01/31/95	Nelson et al.	514	291	
	5,385,632	01/31/95	Goossen	156	630	
	5,420,458	05/30/95	Shimoji	257	622	
	5,424,920	06/13/95	Miyake	361	735	
	5,426,072	06/20/95	Finnila	437	208	
	5,426,363	06/20/95	Akagi et al.	324	239	
	5,432,444	07/11/95	Yasohama et al.	324	240	
	5,432,729	07/11/95	Carson et al.	365	63	
	5,434,500	07/18/95	Hauck et al.	324	67	
	5,451,489	09/19/95	Leedy	430	313	
	5,453,404	09/26/95	Leedy	437	203	
	5,457,879	10/17/95	Gurtler et al.	29	895	
	5,476,813	12/19/95	Naruse	437	132	
	5,489,554	02/06/96	Gates	437	208	
	5,502,667	03/26/96	Bertin et al.	365	51	
	5,512,397	04/30/96	Leedy	430	30	
	5,527,645	06/18/96	Pati et al.	430	5	

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not conformance and not considered. Include copy of this form with next communication to applicant.

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	APPLICANT Glenn J. Leedy	CONFIRMATION NO. 5846
	FILING DATE December 19, 2003	GROUP 2814

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	5,563,084	10/08/96	Ramm et al.	437	51	
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	5,580,687	12/03/96	Leedy	430	5	
	5,581,498	12/03/96	Ludwig et al.	365	63	
	5,582,939	12/10/96	Pierrat	430	5	
	5,583,688	12/10/96	Hornbeck	359	291	
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	5,592,018	01/07/97	Leedy	257	619	
	5,595,933	01/21/97	Heijboer	439	20	
	5,606,186	02/25/97	Noda	257	226	
	5,627,112	05/06/97	Tennant et al.	438	113	
	5,629,137	05/13/97	Leedy	430	313	
	5,633,209	05/27/97	Leedy	435	228	
	5,637,536	06/10/97	Val	438	686	
	5,654,127	08/05/97	Leedy	430	315	
	5,654,220	08/05/97	Leedy	438	25	
	5,656,552	08/12/97	Hudak et al.	438	15	
	5,675,185	10/07/97	Chen et al.	257	774	
	5,694,588	12/02/97	Ohara et al.	395	566	
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	5,773,152	06/30/98	Okonogi	428	446	
	5,786,116	07/28/98	Rolfson	430	5	
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	5,834,334	11/10/98	Leedy	438	107	
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FORM PTO-1449  U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. ELM-1 Cont. 13	APPLICATION NO. 10/724,282
	APPLICANT Glenn J. Leedy	CONFIRMATION NO. 5846
	FILING DATE December 19, 2003	GROUP 2814

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	APPLICANT Glenn J. Leedy		CONFIRMATION NO. 5846	
	FILING DATE December 19, 2003		GROUP 2814	
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